

=> d'his

(FILE 'HOME' ENTERED AT 15:14:39 ON 01 APR 2004)

FILE 'REGISTRY' ENTERED AT 15:14:59 ON 01 APR 2004

L1 SCREEN 970 AND 2067  
L2 STRUCTURE UPLOADED  
L3 QUE L2 AND L1  
L4 50 S L3 SSS SAM

FILE 'JAPIO' ENTERED AT 15:18:26 ON 01 APR 2004

FILE 'HOME' ENTERED AT 15:18:28 ON 01 APR 2004

FILE 'REGISTRY' ENTERED AT 15:19:55 ON 01 APR 2004

L5 SCREEN 2067  
L6 STRUCTURE UPLOADED  
L7 QUE L6 AND L5  
L8 SCREEN 2067  
L9 STRUCTURE UPLOADED  
L10 QUE L9 AND L8  
L11 50 S L10 SSS SAM  
L12 SCREEN 2067  
L13 STRUCTURE UPLOADED  
L14 QUE L13 AND L12  
L15 11 S L14 SSS SAM  
L16 SCREEN 970 AND 2067  
L17 STRUCTURE UPLOADED  
L18 QUE L17 AND L16  
L19 50 S L18 SSS SAM  
L20 SCREEN 2067  
L21 STRUCTURE UPLOADED  
L22 QUE L21 AND L20  
L23 2 S L22 SSS SAM  
L24 109 S L4 OR L11 OR L15  
L25 0 S L24 AND L23

FILE 'CA' ENTERED AT 15:27:24 ON 01 APR 2004

FILE 'HCAPLUS, CAPLUS, USPATFULL' ENTERED AT 15:27:29 ON 01 APR 2004

=> s 125

L26 0 L25

=> s 123

L27 5 L23

=> duplicates remove 127

DUPLICATE PREFERENCE IS 'HCAPLUS, CAPLUS, USPATFULL'

KEEP DUPLICATES FROM MORE THAN ONE FILE? Y/(N):n

PROCESSING COMPLETED FOR L27

L28 3 DUPLICATE REMOVE L27 (2 DUPLICATES REMOVED)

=> d 128 1-3 ibib abs hitstr

L28 ANSWER 1 OF 3 HCAPLUS COPYRIGHT 2004 ACS on STN DUPLICATE 1

ACCESSION NUMBER: 2002:397839 HCAPLUS

DOCUMENT NUMBER: 136:409059

TITLE: Fluorine-containing cycloolefin polymer, photoresist material containing the polymer, and formation of pattern

INVENTOR(S): Hatakeyama, Jun; Watanabe, Atsushi; Harada, Yuji; Kawai, Yoshio; Sasako, Masaru; Endo, Masataka; Kishimura, Shinji; Otani, Michitaka; Miyazawa, Satoru; Tsutsumi, Kentaro; Maeda, Kazuhiko

PATENT ASSIGNEE(S): Shin-Etsu Chemical Industry Co., Ltd., Japan; Matsushita Electric Industrial Co., Ltd.; Central Glass Co., Ltd.

SOURCE: Jpn. Kokai Tokkyo Koho, 25 pp.

CODEN: JKXXAF

DOCUMENT TYPE: Patent

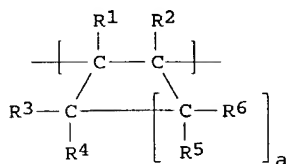
LANGUAGE: Japanese

FAMILY ACC. NUM. COUNT: 1

PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2002155120	A2	20020528	JP 2001-266772	20010904
PRIORITY APPLN. INFO.:			JP 2000-271209	A 20000907

GI



I

AB The polymer has a cycloolefin-derived repeating unit I (R1-R6 = H, F, Cl, C1-20 linear, branched, or cyclic alkyl, fluorinated alkyl;  $\geq 1$  of R1-R6 contain F;  $0 \leq a \leq 10$ ) and another repeating unit having an acid-unstable group. The photoresist contains the polymer and an organic solvent and an acid-generating agent may be further added to the composition to give a chemical-amplified pos.-working photoresist. The composition is applied on a substrate, heated, exposed to high energy beam at 110-190 nm or 1-15 nm wavelength through a photomask, and developed optionally after heating to give a pattern. The photoresist shows enhanced transparency to vacuum UV rays and dry etching resistance.

IT 430427-86-4P

RL: IMF (Industrial manufacture); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)

(fluorine-containing cycloolefin polymer for (chemical-amplified) pos.-working photoresist)

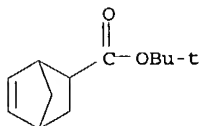
RN 430427-86-4 HCAPLUS

CN Bicyclo[2.2.1]hept-5-ene-2-carboxylic acid, 1,1-dimethylethyl ester, polymer with 2,5-furandione and octafluorocyclopentene (9CI) (CA INDEX NAME)

CM 1

CRN 154970-45-3

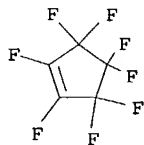
CMF C12 H18 O2



CM 2

CRN 559-40-0

CMF C5 F8



CM 3

CRN 108-31-6

CMF C4 H2 O3



L28 ANSWER 2 OF 3 USPATFULL on STN

ACCESSION NUMBER: 2002:137125 USPATFULL

TITLE: Fluorine-containing copolymer and composition for preparing low reflectance film

INVENTOR(S): Akama, Shuyo, Saitama, JAPAN  
Sugimoto, Hiromi, Saitama, JAPAN  
Tsutsumi, Kentaro, Saitama, JAPAN

PATENT ASSIGNEE(S): Central Glass Company, Limited, Ube, JAPAN (non-U.S.)

corporation)

	NUMBER	KIND	DATE
PATENT INFORMATION:	US 6403744	B1	20020611
APPLICATION INFO.:	US 2000-640536		20000817 (9)

	NUMBER	DATE
PRIORITY INFORMATION:	JP 1999-231687	19990818
	JP 2000-84628	20000324
DOCUMENT TYPE:	Utility	
FILE SEGMENT:	GRANTED	
PRIMARY EXAMINER:	Zitomer, Fred	
LEGAL REPRESENTATIVE:	Crowell & Moring LLP	
NUMBER OF CLAIMS:	19	
EXEMPLARY CLAIM:	1	
NUMBER OF DRAWINGS:	6 Drawing Figure(s); 6 Drawing Page(s)	
LINE COUNT:	954	

CAS INDEXING IS AVAILABLE FOR THIS PATENT.

AB The invention relates to a fluorine-containing copolymer. This copolymer contains 1-99 mol % of a special first repeating unit of a cyclic perfluoro group; and 99-1 mol % of a second repeating unit of a bivalent organic group. The copolymer has a number average molecular weight of from 1,000 to 1,000,000 determined in a gel permeation chromatography using polystyrene as a standard material thereof. The invention further relates to a composition for forming a low reflectance film. This composition contains as a film-forming component a fluorine-containing polymer containing the first repeating unit. This polymer can be the above copolymer. A film formed by applying the composition to a substrate provides low reflectance and is improved in hardness.

CAS INDEXING IS AVAILABLE FOR THIS PATENT.

IT 337488-50-3P, Hydroxyethyl vinyl ether-isobutyl vinyl ether-octafluorocyclopentene copolymer  
(manufacture of fluoropolymers having saturated perfluoro rings with good solubility in organic solvents for transparent films)

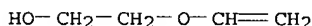
RN 337488-50-3 USPATFULL

CN Ethanol, 2-(ethenyloxy)-, polymer with 1-(ethenyloxy)-2-methylpropane and octafluorocyclopentene (9CI) (CA INDEX NAME)

CM 1

CRN 764-48-7

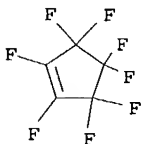
CMF C4 H8 O2



CM 2

CRN 559-40-0

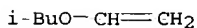
CMF C5 F8



CM 3

CRN 109-53-5

CMF C6 H12 O



L28 ANSWER 3 OF 3 HCAPLUS COPYRIGHT 2004 ACS on STN DUPLICATE 2

ACCESSION NUMBER: 2001:326291 HCAPLUS

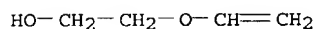
DOCUMENT NUMBER: 134:341129

TITLE: Fluoropolymers having saturated perfluoro rings with good solubility in organic solvents and their manufacture

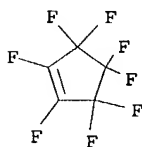
INVENTOR(S): Akama, Hidehiro; Sugimoto, Hiromi; Tsutsumi, Kentaro

PATENT ASSIGNEE(S): Central Glass Co., Ltd., Japan  
 SOURCE: Jpn. Kokai Tokkyo Koho, 12 pp.  
 CODEN: JKXXAF  
 DOCUMENT TYPE: Patent  
 LANGUAGE: Japanese  
 FAMILY ACC. NUM. COUNT: 2  
 PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2001122928	A2	20010508	JP 2000-232570	20000801
PRIORITY APPLN. INFO.:			JP 1999-231687	A 19990818
AB	The fluoropolymers (average mol. weight 1000-1,000,000; measured by gel permeation chromatog.), useful for transparent films, coatings, etc., contain repeating units of (A) 1-99 mol% 1,3- or 1,2-perfluorocyclopentylene and (B) 1-99 mol% divalent organic groups. Thus, an acetone solution of vinyl acetate-octafluorocyclopentene copolymer was applied on a glass plate and dried to give a transparent film.			
IT	337488-50-3P, Hydroxyethyl vinyl ether-isobutyl vinyl ether-octafluorocyclopentene copolymer RL: IMF (Industrial manufacture); PRP (Properties); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses) (manufacture of fluoropolymers having saturated perfluoro rings with good solubility in organic solvents for transparent films)			
RN	337488-50-3 HCAPLUS			
CN	Ethanol, 2-(ethenyloxy)-, polymer with 1-(ethenyloxy)-2-methylpropane and octafluorocyclopentene (9CI) (CA INDEX NAME)			
CM	1			
CRN	764-48-7			
CMF	C4 H8 O2			



CM 2  
 CRN 559-40-0  
 CMF C5 F8



CM 3  
 CRN 109-53-5  
 CMF C6 H12 O

